# Resistive switching in cluster assembled metallic films

#### **Report 1st Year**

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DIPARTIMENTO DI FISICA

# Nanostructured metallic thin films

Why are the electrical properties so interesting?



# Nanostructured metallic thin films

Why are the electrical properties so interesting?

Thin Films atom-assembled — Anomalous properties





Thickness < 1  $\mu$ m • Defects

- Impurities
- Dislocations
- . . .



Scattering events

\*\* Mayadas e Shatzkes, *Phys. Rev. B*, **1**, 1382 (1986)



\* S. B. Arnason et al., *Phys. Rev. Lett.*, **81**, 3936 (1998);



\* S. B. Arnason et al., *Phys. Rev. Lett.*, **81**, 3936 (1998);



\* Sandouk et al., Sci. Technol. Adv. Mater., 16, 055004 (2015);



logic gates, adaptive systems....

\*Strukov et al., *Nature*, **453**, 80 (2008)





size-induced metal-insulator transition



Cluster as building blocks to fabricate film:

- With defects, dislocations...
- Properties different form bulk-like
- Properties different from atomically deposited film

### **Cluster assembled metallic films**



### **Objectives**

- Study the morphology
- Control the growth process
- Understand electrical transport properties

Materials

Hypothesis,

Conclusion Emen

Procedure

### **Experimental methods**

Gain a deeper insight into the methods can be used...



- 1. Cluster metallic film fabrication
- 2. Morphology investigation
- 3. Electrical transport properties investigation

### **Experimental methods**

![](_page_12_Figure_2.jpeg)

### **Experimental methods**

#### AFM, SEM...

![](_page_13_Picture_7.jpeg)

- 1. Cluster metallic film fabrication
- 2. Morphology investigation

3. Electrical transport properties investigation

Some image processing...

..geometrical properties analysis (island size, coverage...)

![](_page_13_Picture_13.jpeg)

![](_page_13_Figure_14.jpeg)

### **Experimental methods**

#### **Voltage-Current measurement**

![](_page_14_Figure_3.jpeg)

![](_page_14_Figure_4.jpeg)

Electrical properties under the application of an external bias

- 1. Cluster metallic film fabrication
- 2. Morphology investigation
- 3. Electrical transport properties investigation

![](_page_15_Figure_0.jpeg)

Introduction	Methods	Results	Discussion	Conclusions
	<b>Per</b>	colation Cu	rve	

![](_page_16_Figure_1.jpeg)

Introduction	Methods	Results	Discussion	Conclusions

![](_page_17_Figure_1.jpeg)

# Native Island Size Distribution

#### Growth in the first stages

![](_page_17_Figure_4.jpeg)

Introduction	Methods	Results	Discussion	Conclusion	
0.01 0.008 0.008		<b>Percolation Threshold</b> Growth in the first stages			
CC(112)		1.8	<del>, , , , , , , , , , , , , , , , , , , </del>		
0.004		1.6 - $\delta_{R} = (R_{eq})$	- R <sub>eq0</sub> )/R <sub>eq0</sub>		
0.002 -	-	1.4 -			
0 5 10 15 20 25 thickne	30 35 40 45 50 ss(nm)	1.2 -		-	
19 8 AMA MANA 13 13		1 -		-	
		∞ <sup>™</sup> 0.8 -	Lateral growth	1 -	
		0.6		-	
12.58 J. 1. 1. 1. 1. 1. 1. 1. 1. 1. 1. 1. 1. 1.	and the second second	0.4 -	F	-	
26 26 8 20 1		0.2 -	, ⊢ <u>∓</u> − i	-	
		0		_	
Mag = 300.00 K X 100 nm WD = 4.1 mm EHT = 7 Date 29 May 2019 Signa A	200 kV NEMAS Number Number Newards and Surfaces N ■ Talens POI (TFC/RC) D1 M1 AND	-0.2 0.05 0.1 0.	.15 0.2 0.25 0.3 0.35	5 0.4 0.45 0.5	
			coverage		

![](_page_19_Figure_0.jpeg)

 $R(\Omega)$ 

Chloé Minnai, Matteo Mirigliano, Simon A Brown and Paolo Milani: The nanocoherer: an electrically and mechanically resettable resistive switching device based on gold clusters assembled on paper, *Nano Features* (2018)

Introduction	Methods	Results	Discussion	Conclusions

![](_page_20_Figure_1.jpeg)

![](_page_20_Picture_2.jpeg)

### **Beyond the Percolation Threshold** Morphology

![](_page_21_Figure_0.jpeg)

### Discussion

At the origins of the non linear behaviour and the switching mechanism in our metallic systems

![](_page_22_Picture_5.jpeg)

Presence of defects, grain boundaries...

Different conduction mechanisms: tunnelling...

#### Electromigration effects

Joule heating, atom rearrangements....

![](_page_22_Figure_10.jpeg)

"As grains are growing and restructuring, there is the possibility for grain boundary potentials to alter in both height and width so to either increase or decrease the resistance"

Durkun, Schneider, Welland J. Appl. Phys., 86 (1999)

![](_page_22_Picture_13.jpeg)

![](_page_23_Figure_0.jpeg)

Introduction

Methods

Results

Discussion

### Conclusions

Cluster assembled metallic films

# Fundamental point of view

- Organization of the matter at the nanoscale
- Growth morphology
- Understanding of physical properties like electrical transport

## Applications

- Non linear electrical properties
- Switching mechanism in metallic films

Introduction

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#### Methods

Results

Cluster assembled metallic films

- Organization of the matter at the nanoscale
- Growth morphology
- Understanding of physical properties like electrical transport
- Non linear electrical properties
- Switching mechanism in metallic films

# Conclusions

Perspectives

Image: constrained of the section o

Deepest study of switching behaviour

- Exploiting such a complex phenomena
  - Further study on local electrical and morphological properties of thicker films (AFM)

I	ntroduction	Methods	Results	Discussion	Conclusions
	This is high	ly multidisciplinary proje Thanks to:	ct		DIPARTIMENTO DI FISICA
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### **Thanks for attention!**

![](_page_26_Picture_3.jpeg)

![](_page_26_Picture_4.jpeg)

Introduction	Methods	Results	Discussion	Conclusions
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## SLIDE DI RISERVA

### Experimental methods Image processing

#### **Thresholding method**

![](_page_28_Figure_7.jpeg)

Introduction

### Experimental methods Image processing

![](_page_29_Picture_6.jpeg)

Diameter of a circle with the same area as the region, returned as a scalar. Computed as sqrt(4\*Area/pi).

![](_page_29_Figure_8.jpeg)

- Perimeter
- Area
- Equivalent diameter =  $sqrt(Area/\pi)$

#### **Experimental methods** Electric Measurements

![](_page_30_Figure_6.jpeg)

Scheme of the device under test

Two probes method

V = R I

V: voltage R: resistance I: current

### **Beyond the Percolation Threshold** Granulometry

![](_page_31_Picture_6.jpeg)

![](_page_31_Figure_7.jpeg)

![](_page_31_Figure_8.jpeg)

Segmentation under same constraints on curvature radius

![](_page_32_Figure_0.jpeg)

0.1

0.05

30.8

30.85

![](_page_32_Figure_1.jpeg)

![](_page_32_Figure_2.jpeg)

**Before switch** 

After switch

 $low - high - low \rightarrow voltage$